

IrO₂

Oxide **IRIDIUM** SPUTTERING TARGET

Iridium oxide sputtering target is used for thin film deposition, typically for fuel cell, decoration, semiconductor, display, LED and photovoltaic devices, glass coating, etc. IrO₂ is also used with other rare oxides, such as titanium nitride or iridium oxide, in the coating of anode-electrodes for industrial electrolysis and in microelectrodes for electrophysiology research.

Quick Facts

Product	:	Iridium Sputtering Target
Stock No	:	NS6130-10-1406
CAS	:	12030-49-8
Backing Plate	:	(As per Customer requirement)

Additional Characteristics

Stock No.	Purity	Diameter	Thickness
NS6130-10-1406	99.99%	50.8 mm ± 1mm	3 mm ± 0.5mm

Technical Specification

Molecular Formula	Molecular Weight	Melting Point
IrO ₂	224.22g/mol	2410°C



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High Purity
SPUTTERING

TARGET



20ZICE4589C



19ZAZGO1274G



20ZICE4588M

ISO 9001:2015
CERTIFIED COMPANY